



## Special Seminar

### Nonadiabatic molecular dynamics investigations on the ultrafast charge dynamics at Interfaces

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**Time: 2:00pm, July 19, 2016 (Tuesday)**

**2016 7 19**

**2:00**

**Venue: Room W563, Physics building, Peking University**

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The ultrafast dynamics of photo-excited charge carriers plays an important role in optoelectronics and solar energy conversion. Using nonadiabatic molecular dynamics simulation, we study the ultrafast charge dynamics at  $\text{CH}_3\text{OH}/\text{TiO}_2$  and  $\text{MoS}_2/\text{WS}_2$  interfaces. For  $\text{CH}_3\text{OH}$ , we study the forward and backward hole transfer between  $\text{TiO}_2$  and  $\text{CH}_3\text{OH}$  as well as the whole hole relaxation process to valence band maximum (VBM). First, we found that the hole trapping ability of  $\text{CH}_3\text{OH}$  depends on the adsorption structure strongly. Only when the  $\text{CH}_3\text{OH}$  is deprotonated to form chemisorbed  $\text{CH}_3\text{O}$ , there will be ~15% hole trapped by the molecule. Second, we found the time scales of forward hole transfer process from  $\text{TiO}_2$  to  $\text{CH}_3\text{O}$  (hole trapping process) and hole relaxation to VBM strongly depend on the temperature. When the temperature decreases from 300K to 30K, for hole trapping process, the time scale increases from 150 fs to ps magnitude. The hole relaxation process to VBM is also slow down significantly. This can be interpreted by the reduction of the non-adiabatic coupling and the phonon occupation. Our studies provide valuable insights into the photogenerated charge dynamics near molecule/ $\text{TiO}_2$  interface.

For  $\text{MoS}_2/\text{WS}_2$ , we show that instead of direct tunneling, the ultrafast interlayer hole transfer is strongly promoted by an adiabatic mechanism through phonon excitation. At room temperature the interlayer charge transfer in  $\text{MoS}_2/\text{WS}_2$  is ultrafast with a timescale of 20 fs which is in good agreement with the experiment. This ultrafast hole transfer process can be suppressed by decreasing the temperature to 100K, which reduces the phonon occupation and the charge transfer is then dominated by direct tunneling, which happens at the time scale longer than 300 fs. The atomic level picture of phonon-assisted ultrafast mechanism revealed in our study is valuable both for the fundamental understanding of ultrafast charge carrier dynamics at vdW hetero-interfaces as well as for the design of novel quasi-2D devices for optoelectronic and photovoltaic applications.

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